

ABSTRACT

The present disclosure belongs to the field of semiconductor technology, and particularly relates to a gas intake system for a semiconductor process device, a semiconductor process device, and a gas intake method. The gas intake system includes a water storage tank, a gas storage tank, a water vapor conveying pipeline, and a gas supply pipeline, the water storage tank is provided with a water inlet port capable of being opened and closed, a first heating device is disposed on the water storage tank, two ends of the water vapor conveying pipeline are respectively in on-off communication with a gas outlet of the water storage tank and a gas inlet of the gas storage tank, the gas storage tank is in on-off communication with a process chamber of the semiconductor process device through the gas supply pipeline, and in a case where one of the water inlet port and the water vapor conveying pipeline is in an on state, the other is in an off state. The present disclosure can improve intake stability of water vapor.